

Fig. 1

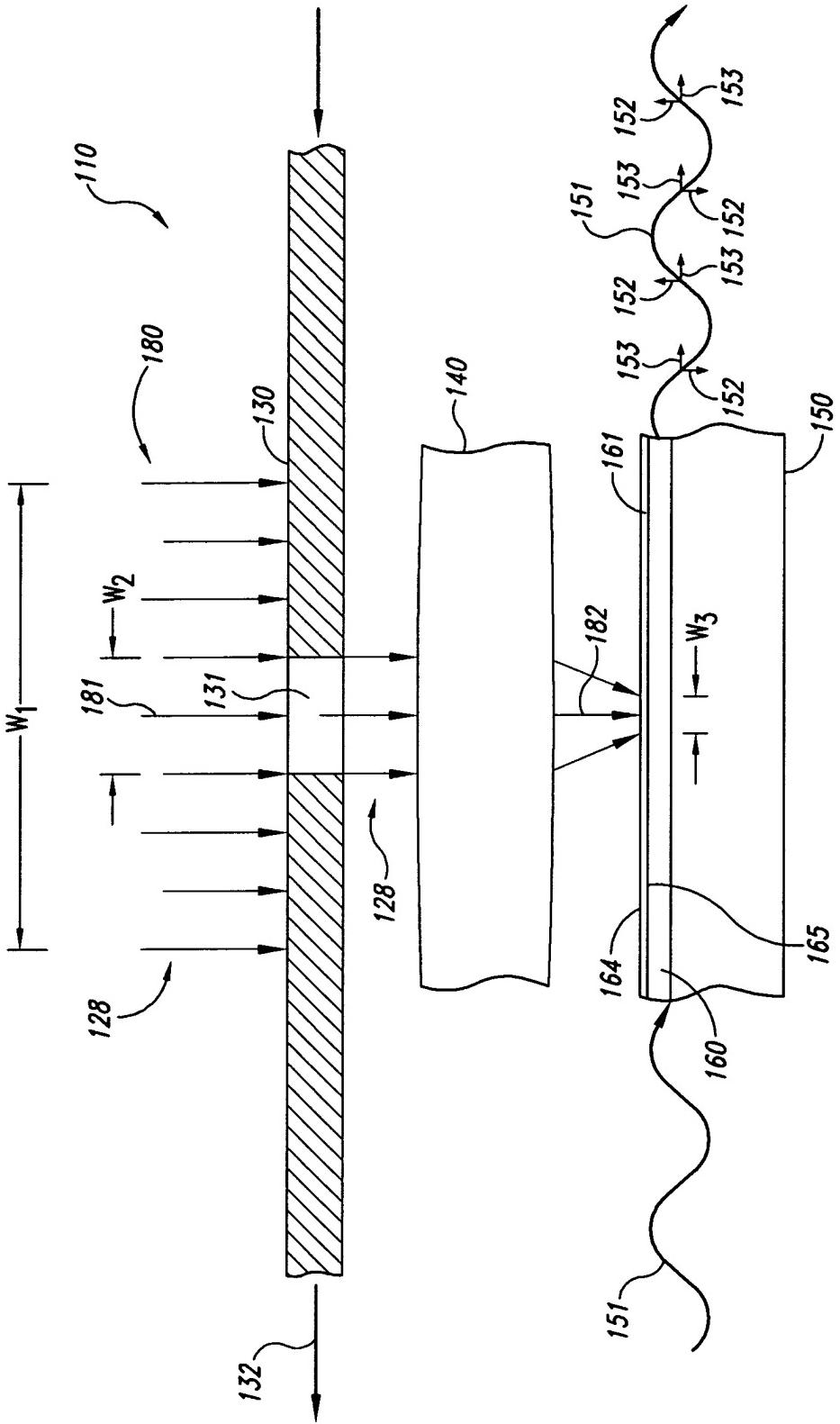


Fig. 2

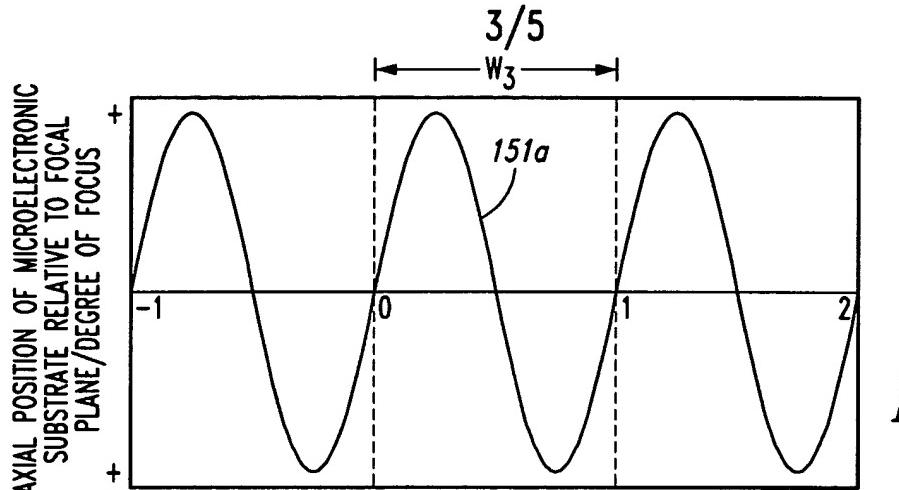


Fig. 3A

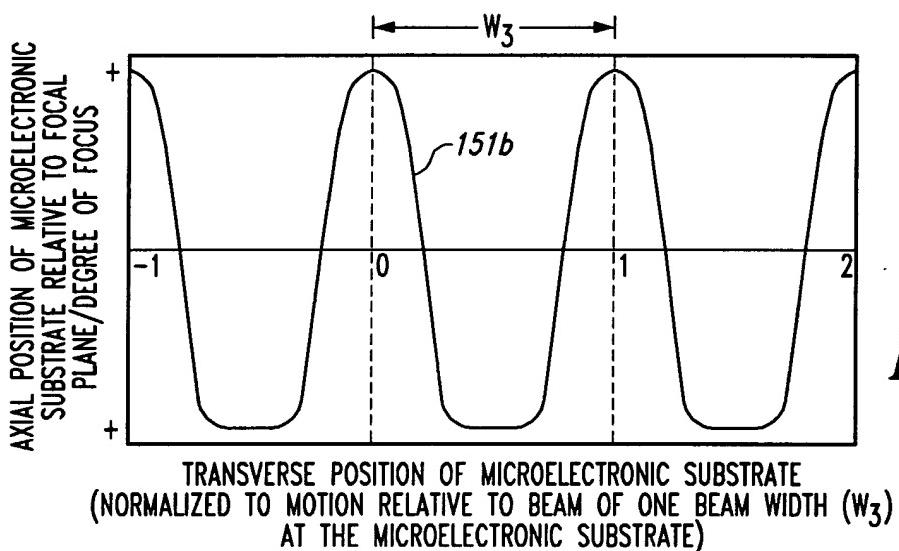


Fig. 3B

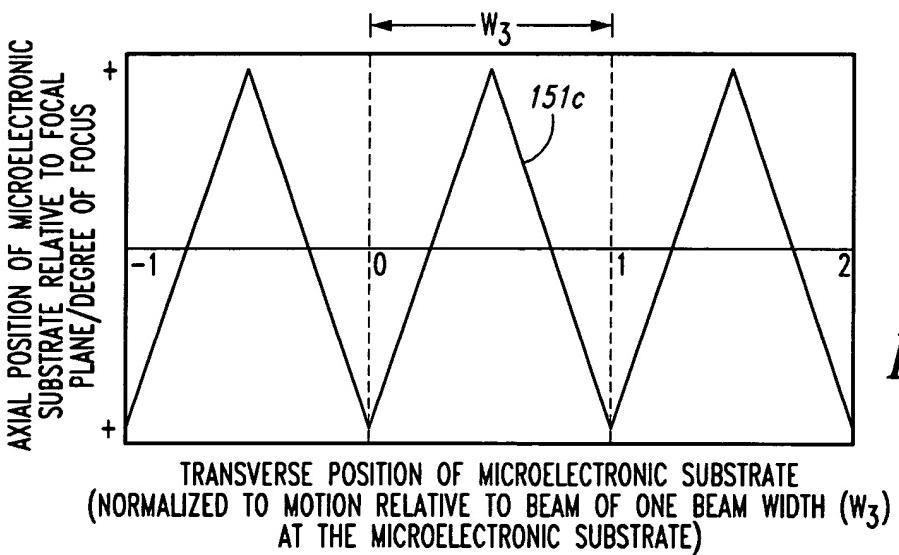


Fig. 3C

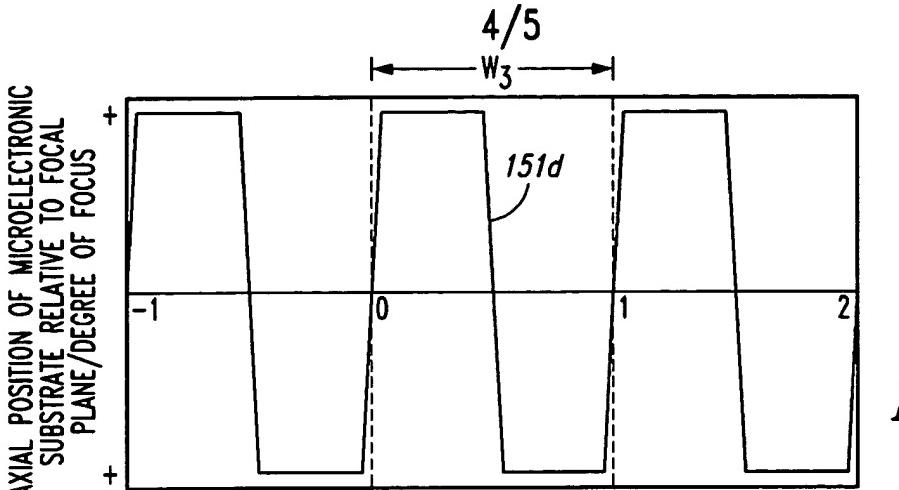


Fig. 3D

TRANSVERSE POSITION OF MICROELECTRONIC SUBSTRATE
(NORMALIZED TO MOTION RELATIVE TO BEAM OF ONE BEAM WIDTH (W_3)
AT THE MICROELECTRONIC SUBSTRATE)

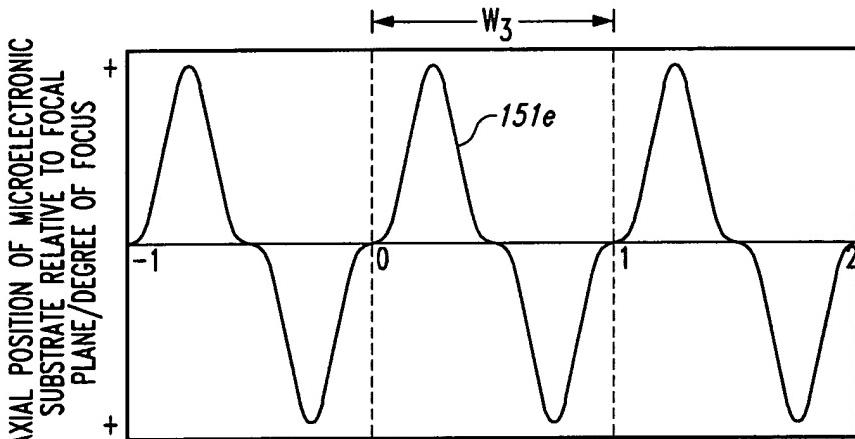


Fig. 3E

TRANSVERSE POSITION OF MICROELECTRONIC SUBSTRATE
(NORMALIZED TO MOTION RELATIVE TO BEAM OF ONE BEAM WIDTH (W_3)
AT THE MICROELECTRONIC SUBSTRATE)

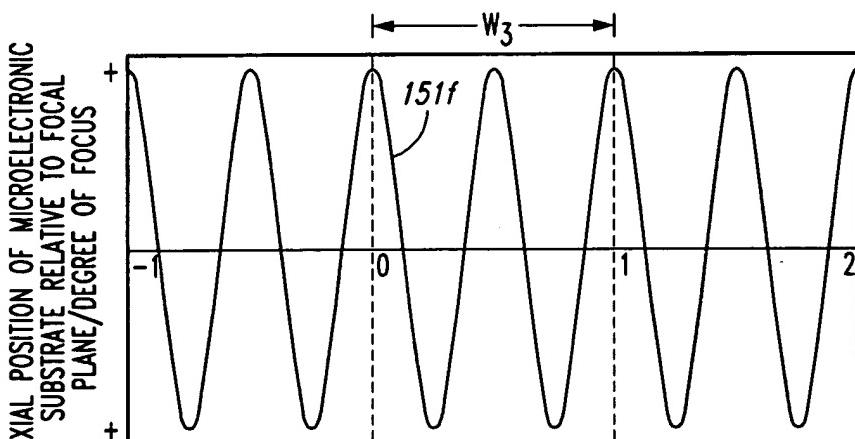


Fig. 3F

TRANSVERSE POSITION OF MICROELECTRONIC SUBSTRATE
(NORMALIZED TO MOTION RELATIVE TO BEAM OF ONE BEAM WIDTH (W_3)
AT THE MICROELECTRONIC SUBSTRATE)

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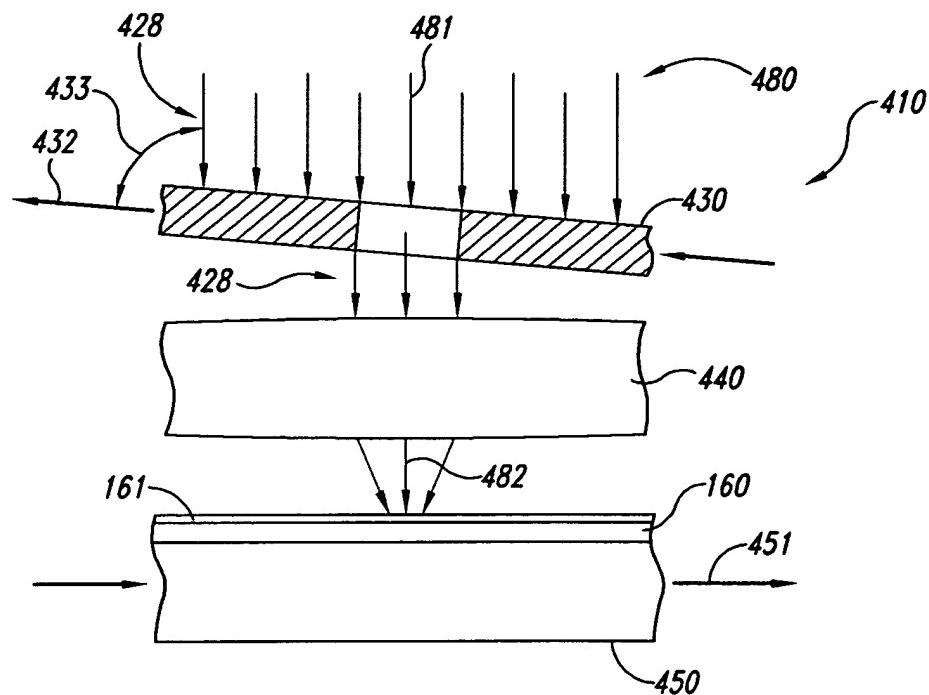


Fig. 4

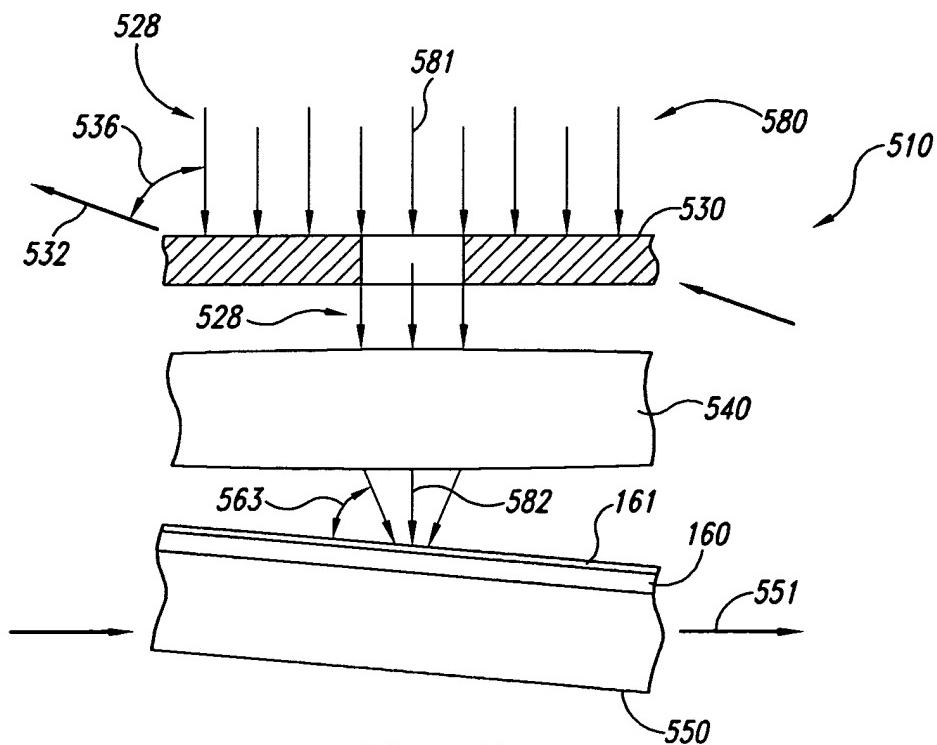


Fig. 5